

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Josephson et al.

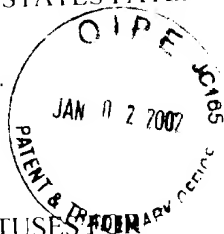
Application No. 09/905,654

Filed: July 11, 2001

For: PROCESSES AND APPARATUSES FOR
TREATING HALOGEN-CONTAINING GASES

Examiner: Not yet assigned

Date: October 26, 2001



Art Unit: 1725

CERTIFICATE OF MAILING

I hereby certify that this paper and the documents referred to as being attached or enclosed herewith are being deposited with the United States Postal Service on October 26, 2001 as First Class Mail in an envelope addressed to: BOX MISSING PARTS, COMMISSIONER FOR PATENTS, WASHINGTON, D.C. 20231.

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INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 C.F.R. § 1.97(b)(3)

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Sir:

Listed on the accompanying form PTO-1449 and enclosed herewith are several English-language documents. Applicants respectfully request that these documents be listed as references cited on the issued patent.

Applicants filed this Information Disclosure Statement ("IDS") before the mailing date of a first Office action on the merits. As a result, no fee should be required to file this IDS. However, if the Patent Office determines that a fee is required for Applicants to file this Information Disclosure Statement, please charge any such fees, or credit overpayment, to Deposit Account No. 02-4550. A **duplicate** copy of this Information Disclosure Statement is enclosed.

Respectfully submitted,

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Docket: 23-59123		App: 09/905.654	
				Applicant: Josephson et al.			
				Filed: July 11, 2001		Art Unit: 1725	
U.S. PATENT DOCUMENTS							
Init.*		Number	Date	Name	Class	Sub	Filed
FOREIGN PATENT DOCUMENTS							
		Number	Date	Country	Class	Sub	
OTHER DOCUMENTS							
			Lester, "Clean Processing. No More PFC Emissions in Plasma Chamber Cleaning?" <i>Semiconductor</i> , p. 46 (2000)				
			Rosenthal et al., "Corona Discharge for Surface Treatment," <i>IEEE Trans. Ind. Appln.</i> , I-5, 328-335 (1975)				
			Timms et al., "The chemistry of volatile waste from silicon wafer processing," <i>J. Chem. Soc.</i> , pp. 815-822 (1999)				
			Vartanian et al., "Plasma Abatement Reduces PFC Emission," <i>Semiconductor International</i> , pp. 191-198 (2000)				
EXAMINER:				DATE			
*Examiner: Initial if considered, whether or not in conformance with MPEP 609; draw line through cite if not in conformance and not considered. Send copy.							

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Docket: 23-59123	App: 09/905,654
	Applicant: Josephson et al.	
	Filed: July 11, 2001	Art Unit: 1725

U.S. PATENT DOCUMENTS

Init.*	Number	Date	Name	Class	Sub	Filed
	4,489,041	12/18/1984	Wong et al.			
	5,187,344	02/16/1993	Mizuno et al.			
	5,817,284	10/09/1998	Nakano et al.			
	5,980,701	11/09/1999	Sharma et al.			
	6,187,072	02/13/2001	Cheung et al.			
	6,193,934	02/27/2001	Yang			

FOREIGN PATENT DOCUMENTS

	Number	Date	Country	Class	Sub	

OTHER DOCUMENTS

		Evans et al., "Plasma remediation of trichloroethylene in silent discharge plasmas," <i>J. Appl. Phys.</i> 74:9 pp. 5378-5387 (1993)
		Flippo et al., Abatement of Fluorine Emissions Utilizing an ATMI CDO™ Model 863 with Steam Injection (2001)
		Grothaus et al., "Harmful Compounds Yield to Nonthermal Plasma Reactor," <i>SwRI Technology Today</i> , http://www.swri.org , pp. 1-9 (published in <i>Technology Today</i> , Spring 1996)
		International Sematech Disclosure, "Evaluation of a Litmas "Blue" point-of-Use (POU) Plasma Abatement Device for Perfluorocompound (PFC) Destruction," Technology Transfer No. 98123605A-Eng (December 15, 1998)

EXAMINER:

DATE

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